



900 - 600 Deposition Tool



Batch Processing
PVD System
Sputter Deposition

First developed by ESC back in 1995, this versatile deposition system is aimed at the thin-film market.

This flexible solution is easily configurable to meet the end users individual requirements.

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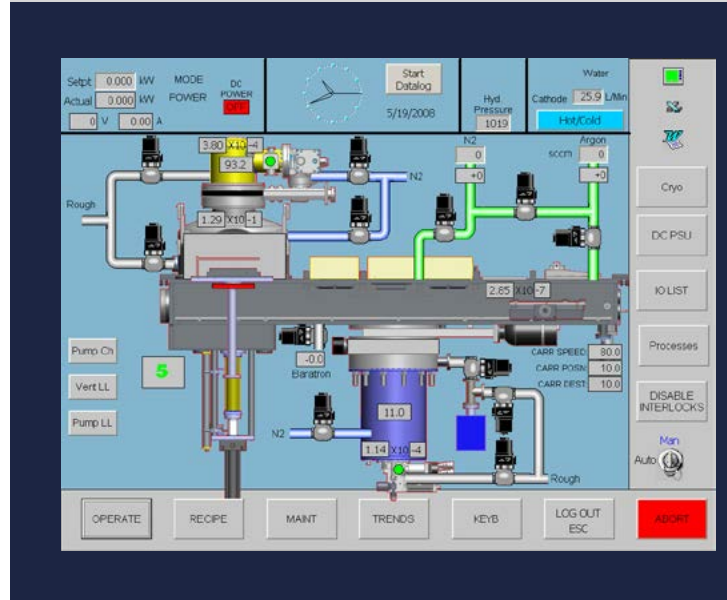
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Deposition Chamber Options

- Downwards or (900) horizontal (600) sputtering
- RF, DC or Pulsed DC sputtering
- Ion beam milling
- Reactive sputtering
- In process monitoring
- Turbo pump or cryo pump
- Up to five process gases, either chamber fed or at the cathode
- Wide variety of substrate sizes including mixed batches on pallet sizes up to 317mm square
- Substrate bias RF or DC

Load Lock Options

- Low vacuum, backing pump only
- High vacuum, turbo pump or cryo pump
- Substrate RF etch
- Substrate heat
- Single substrate or multiple substrate



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